

REMARKS

Claims 1-16 are pending in the present application.

Applicants acknowledge with appreciation the Examiner's indication that claims 4, 5, 10, and 13-15 contain allowable subject matter. With reference to the remarks below, applicants respectfully submit that base claims 1 and 8, from which these claims depend, are also allowable in view of the cited prior art, and respectfully request that these claims be allowed.

Claims 1, 2, 6-9, 11, and 16 stand rejected under 35 U.S.C. § 102(b) as being anticipated by U.S. Patent No. 5,747,857 to Eda et al. Applicants respectfully traverse the rejection.

Eda et al., as relied upon by the Examiner, describe an anodic bonding process that includes the steps of: 1) polishing and cleaning a silicon substrate and quartz plate; 2) directly contacting the silicon substrate and quartz plate; and 3) applying a voltage to the interface between them while heating the interface to bond the surfaces by electrostatic attraction. (Please see col. 40, lines 5-8 of Eda et al.) Since the electrostatic attraction of this anodic bonding process of Eda et al. is mainly caused by small electrostatic polarization in the silicon and quartz crystal, it is weak across the interface and the resulting bonding strength is relatively small in comparison to that of the claimed invention.

Significantly, applicants respectfully submit that Eda et al., as relied upon by the Examiner, fail to disclose,

"a cover having a shape with a recessed part and made of glass containing ions having high mobility," as recited in claim 1.
(Emphasis added)

Applicants refer to page 10, lines 3-7 and page 12, lines 23-26 of the specification for exemplary embodiments of the above-cited feature of the claimed invention. Advantageously,

since the cover contains ions having high mobility, the electrostatic attraction at the interface between the cover and the substrate is strong and a large bonding strength is achieved. This feature is not considered in the cited portions of Eda et al. Furthermore, the use of quartz, which is a crystalline of pure silicon dioxide, as described in the cited portions of Eda et al. is not suitable for the cover of the claimed invention.

Applicants, therefore, respectfully submit that claim 1, together with claims 2 and 6 dependent therefrom, is patentable over Eda et al. Independent claim 8 includes limitations similar to those of claim 1 discussed above, and is, therefore, together with claims 9, 11, and 16 dependent therefrom, patentable over Eda et al. for at least the same reasons.

The Examiner rejected claim 7 based on Eda et al., but the cited portions of Eda et al. do not disclose the features recited in claim 7. The Examiner has apparently not specifically addressed how the cited reference anticipates the limitations of claim 7. Applicants submit that claim 7 is patentable over the cited reference, and request that the Examiner kindly provide the grounds for rejecting claim 7. Applicants respectfully request that such grounds be provided in a non-final Office Action.

Claims 3 and 12 stand rejected under 35 U.S.C. § 103(a) as being unpatentable over Eda et al. in view of U.S. Patent No. 5,952,894 to Fukiharu. The Examiner applied Fukiharu as a combining reference specifically for teaching the additional limitations of dependent claims 3 and 12. Therefore, even assuming, arguendo, that it would be obvious to one skilled in the art to combine the references in the manner proposed by the Examiner, the combination would still fail to disclose the features of base claim 1 discussed above. Applicants, therefore, respectfully submit that claims 3 and 12 are patentable over the cited references for at least the reasons stated above with respect to base claim 1.

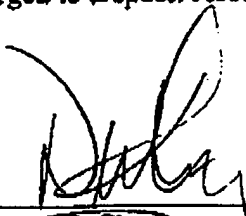
Statements appearing above in respect to the disclosures in the cited references represent the present opinions of the undersigned attorney and, in the event that the Examiner disagrees with any of such opinions, it is respectfully requested that the Examiner specifically indicate those portions of the respective reference providing the basis for a contrary view.

The Examiner has made of record, but not applied, several additional U.S. patents. Applicants appreciate the Examiner's implicit finding that these references, whether considered alone or in combination with others, do not render the claims of the present application unpatentable.

In view of the remarks set forth above, this application is in condition for allowance which action is respectfully requested. However, if for any reason the Examiner should consider this application not to be in condition for allowance, the Examiner is respectfully requested to telephone the undersigned attorney at the number listed below prior to issuing a further Action.

Any fee due with this paper may be charged to Deposit Account No. 50-1290.

Respectfully submitted,



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